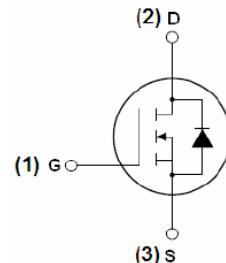


## N-Channel PowerMOSFET Wafer Datasheet

### FEATURES

- 2500V、0.5A\*, N-channel
- $R_{DS(on)}=200.0\Omega(\text{MAX})$
- Ultra low  $Q_{gd}$
- Fast switching



### Electrical Characteristics( $T_J=25^\circ\text{C}$ )

Parameter	Description	Min.	Typ.	Max.	Unit	Test Condition
$V_{(\text{BR})\text{DSS}}$	Drain-Source Breakdown Voltage	2500			V	$\text{VGS}=0\text{V}, \text{ID}=-250\mu\text{A}$
$R_{DS(\text{on})1}$	Static Drain-Source On-Resistance			200.0	$\Omega$	$\text{VGS}=10\text{V}, \text{ID}=0.25\text{A}$
$V_{GS(\text{th})}$	Gate Threshold Voltage	2.5		4.5	V	$\text{VDS}=\text{VGS}, \text{ID}=-250\mu\text{A}$
$I_{DSS}$	Drain-to-Source Leakage Current			10	$\mu\text{A}$	$\text{VDS}=2500\text{V}, \text{VGS}=0\text{V}, \text{TJ}=25^\circ\text{C}$
$I_{GSS}$	Gate-Body Leakage Current			$\pm 100$	nA	$\text{VGS}=\pm 30\text{V}$
$V_{SD}$	Body Diode Voltage			2.0	V	$\text{VGS}=0\text{V}, \text{ISD}=0.5\text{A}$
$T_J, T_{\text{stg}}$	Operating and Storage Temperature Range	-55~+150		°C		

### Mechanical Data

Die Size	6000×3750	$\mu\text{m}^2$	
Gate Pad Size	380×480		
Source Pad Size	No Passivation		
Scribe Line Size	80		
Wafer Diameter	150	μm	
Wafer Thickness	400	μm	
Passivation Frontside	No	---	
Source Metallization	AL	4.0	
Drain Metallization	Ti- Ni - Ag	1.3	
Reject Ink Dot Size	0.51	mm	
Recommended Storage Environment	Store in original container, in dessicated nitrogen, with no contamination		

\* Electrical characteristics are reported for the reference packaged part (TO-220) and can not be guaranteed in die sales form.

Variations in customer packaging materials, dimensions and processes may affect parametric performance.